



Sheet 1 of 1

PTO-1449 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. 213.003-D2-US	SERIAL NUMBER 10/763,142
	APPLICANT(S) Ye et al.	
	FILING DATE January 22, 2004	GROUP ART UNIT 2425 2857

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<i>ER</i>	5,907,820	5/1999	Pan			
	5,967,661	10/1999	Renken et al.			
	6,033,922	3/2000	Rowland et al.			
	6,051,443	4/2000	Ghio et al.			
	6,244,121	6/2001	Hunter			
	6,630,995	10/2003	Hunter			
	6,693,708	2/2004	Hunter			
	6,707,545	3/2004	Hunter			
	6,721,045	4/2004	Hunter			

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<i>QR</i>	4,585,342	4/1986	Lin et al.			
	4,701,606	10/1987	Tanimoto et al.			
	4,929,083	5/1990	Brunner			
	5,202,748	4/1993	MacDonald et al.			
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	5,629,772	5/1997	Ausschnitt			
	5,631,731	5/1997	Sogard			
	5,795,688	8/1998	Burdorf et al.			
	5,828,455	10/1998	Smith et al.			
	5,888,675	3/1999	Moore et al.			
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	5,969,639	10/1999	Lauf et al.			
	5,978,085	11/1999	Smith et al.			
	6,268,093	7/2001	Kenan et al.			
<i>✓</i>	6,335,220	1/2002	Shioyama et al.			

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<i>ER</i>	6,356,345	3/2002	McArthur et al.			
	2001/0055415	12/2001	Nozaki			
	2002/0003216	1/2002	Kida et al.			
	2002/0005947	1/2002	Golberg et al.			
	2002/0036775	3/2002	Wolleschensky et al.			
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	2002/0062206	5/2002	Liebchen			
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	5,597,868	1/1997	Kunz			
	5,914,774	6/1999	Ota			
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<i>AW</i>	6,040,936	3/2000	Kim et al.			
	6,052,238	4/2000	Ebbesen et al.			
	6,236,033	5/2001	Ebbesen et al.			
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	6,278,101	8/2001	Puyot			
	6,285,020	9/2001	Kim et al.			
	6,360,012	3/2002	Kreuzer			
	6,362,907	3/2003	Stone et al.			
	6,368,763	4/2002	Drksen et al.			
	6,515,272	2/2003	Fontaine et al.			
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	2002/0122187	9/2002	Bruce et al.			
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<i>DM</i>	2002/0167651	11/2002	Boonman et al.			
	2002/0172876	11/2002	Baselmans			
	2003/0001107	1/2003	Kroon et al.			
	2003/0017805	1/2003	Yeung et al.			
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	5,491,724	2/1996	Altes			
	5,638,211	6/1997	Shiraishi			
	5,700,601	12/1997	Hasegawa et al.			
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<i>ENC</i>	6,451,490	9/2002	Advocate et al.			
	6,534,798	3/2003	Scherer et al.			
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	2003 0027366	2/2003	Dulman et al.			
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<i>EW</i>	EP 0 628 806	4/1994	European			
<i>J</i>	WO 00/59206	10/2000	PCT			
<i>J</i>	WO 02/17030	2/2002	PCT			

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<i>EW</i>	"A New Mask Evaluation Tool, the Microlithography Simulation Microscope Aerial Image Measurement System", Budd, et al., SPIE Vol. 2197, 1994, pp.530-540
<i>J</i>	"Characterization of Lithographic System Performance Through Direct Aerial Image Measurements", C.H. Fields, SRC/SEMATECH, 1996 (96-MC-500)
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	"Meeting the Challenge of Advanced Lithography Reticle Inspection", Zurbrick et al., SPIE Vol. 2322, Photomask Technology and Management, 1994, pp.7-15
<i>J</i>	"In Situ Resolution and Overlay Measurement on a Stepper", Brunner et al., SPIE Vol. 565, Micron and Submicron Integrated Circuit Metrology, 1985, pp.6-13

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<i>am</i>	"Application of the Aerial Image Measurement System (AIMS™) to the Analysis of Binary Mask Imaging and Resolution Enhancement Techniques", Martino et al., SPIE Vol. 2197, 1994, pp.573-584
	"Optical Limitations to Cell Size Reduction in IT-CCD Image Sensors", Satoh et al., IEEE, Transactions on Electron Devices, Vol. 44, No. 10, Oct. 1997, pp.1599-1603
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<i>V</i>	"Near-Field Optics: Microscopy, Spectroscopy, and Surface Modification Beyond the Diffraction Limit", Betzig and Trautman, Science, Vol. 257, July 1992, pp.189-195

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<i>aw</i>	"Direct Aerial Image Measurement as a Method of Testing High Numerical Aperture Microlithographic Lenses", Partlo et al., Journal of Vacuum Science Technology B, Vol. 6, No. 11, Nov/Dec 1993, pp.2686-2691
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	"A Multi-Blanker for Parallel Electron Beam Lithography", G. Winograd, Ph.D. Dissertation, Stanford University, May, 2001
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	2002/0177916	11/2002	Poolla et al.			
	2002/0177917	11/2002	Polla et al.			
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	2003/0020917	1/2003	Mundt et al.			
	2003/0222049	12/2003	Mundt			
	6,160,621	12.2000	Perry et al.			
	6,432,729	8/2002	Mundt et al.			
	6,582,619	6/2003	Mundt			
	6,642,063	11/2003	Mundt et al.			
<i>X</i>	6,671,660	12/2003	Freed			

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	5,830,372	11/1998	Hierold, Christopher			
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